

(19) World Intellectual Property
Organization
International Bureau



(43) International Publication Date
8 April 2004 (08.04.2004)

PCT

(10) International Publication Number
WO 2004/030038 A3

(51) International Patent Classification⁷: **G03C 5/00**,
C25F 5/00, 1/00, 3/30, B08B 6/00, C03C 23/00, C23G
1/00, 1/02

(21) International Application Number:
PCT/US2003/030237

(22) International Filing Date:
26 September 2003 (26.09.2003)

(25) Filing Language: English

(26) Publication Language: English

(30) Priority Data:
10/254,785 26 September 2002 (26.09.2002) US

(81) Designated States (*national*): AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW.

(84) Designated States (*regional*): ARIPO patent (GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW), Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European patent (AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PT, RO, SE, SI, SK, TR), OAPI patent (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

(71) Applicant (*for all designated States except US*): **AIR PRODUCTS AND CHEMICALS, INC.** [US/US]; 7201 Hamilton Boulevard, Allentown, PA 18195 (US).

(72) Inventor; and

(75) Inventor/Applicant (*for US only*): **EGBE, Matthew** [US/US]; 122 Flannery Drive, West Norriton, PA 19403 (US).

(74) Agent: **AMERNICK, Burton, A.**; Connolly Bove Lodge & Hutz LLP, 1990 M Street, N.M., Suite 800, Washington, DC 20036-3425 (US).

Published:

- with international search report
- before the expiration of the time limit for amending the claims and to be republished in the event of receipt of amendments

(88) Date of publication of the international search report:
8 July 2004

For two-letter codes and other abbreviations, refer to the "Guidance Notes on Codes and Abbreviations" appearing at the beginning of each regular issue of the PCT Gazette.

(54) Title: COMPOSITIONS SUBSTRATE FOR REMOVING ETCHING RESIDUE AND USE THEREOF

(57) Abstract: Compositions containing certain organic solvents and a fluorine source are capable of removing photoresist and etching residue.



WO 2004/030038 A3